Realizing a high-intensity low-emittance beam in the J-PARC 3-GeV RCS

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J-PARC 3-GeV Rapid Cycling Synchrotron (RCS)

Circumference	348.333 m	000-000-00-00-00-00-00-00-00-00-00-00-0	2-NDT Extraction
Superperiodicity	3 Injectio	on stranger	beam dump
Harmonic number	2 beam of	dump	(8 kW)
Number of bunches	2 (4 kW		
Injection	Multi-turn,	Secondary collimators	
	Charge-exchange	Primary collimator	<u>3-GeV</u>
Injection energy	400 MeV	Injection section	protons
Injection period	0.5 ms (307 turns)	(Injection point)	to MR
Injection peak	50 mA		2 CODU
current			3-20B1
Extraction energy	3 GeV	RF	cavities
Repetition rate	25 Hz	L-3BT	
Particles per pulse	8.33 x 10 ¹³		
Beam power	1 MW	inac 400-Mev H ⁻	

- ✓ RCS has two functions as;
 - Proton driver for producing pulsed muon and neutrons at MLF,
 - Injector to MR.
- ✓ The requirements for the beam operations to MLF and MR are different. Thus, different parameter optimizations are required for each.

Requirements for

the beam operation to MLF

- Machine activations of RCS are mainly determined by the beam operation to MLF.
 - \Rightarrow Sufficient beam loss mitigation
- To ensure a sufficient life-time of the neutron target at MLF, a shockwave on the neutron target has to be mitigated.
 - ⇒ Wide-emittance beam with less charge density

Reported in IPAC'16

- Successfully demonstrated a 1-MW beam operation to MLF
 - Wide-ranging transverse injection painting
 - (ϵ_{tp} =200 π mm mrad)
 - Betatron resonance correction
 - RF power supply upgrade



- ✓ The output beam power for MLF;
 - is now temporally limited to 150 kW due to a malfunction of the neutron target.
 - will be increased gradually toward 1 MW after installing a new target this summer.
- ✓ The accelerator itself is now ready to test a continuous 1-MW beam operation to MLF.

Requirements for the beam operation to MR

D Beam loss mitigation in MR

 \Rightarrow A low-emittance beam with less beam halo

Beam tuning for the beam operation to MR;

- ✓ Optimizations of;
 - transverse injection painting for minimizing emittance growth during injection
 - tune & chromaticity manipulations over the acceleration process for mitigating additional emittance growth during acceleration
 - Beam intensity; ~7.0 x 10¹³ ppp (~84% of the RCS design intensity) corresponds to the MR beam power of ~535 kW for a operation cycle of 2.48 s

Main topic of this talk;

- Recent efforts for realizing a high-intensity low-emittance beam required from MR
- Discussions for the emittance growth and its mitigation mechanisms

Optimization of transverse injection painting

for minimizing emittance growth during injection



(a)+(c) \Rightarrow Anti-correlated painting

Painting emittance; $\varepsilon_{tp} = 0 \sim 216 \pi$ mm mrad

To minimize emittance growth during injection, we optimized transverse injection painting.

Painting parameter dependence of the beam width



✓ The minimum beam width is achieved for a small painting emittance of ε_{tp} ~50 π mm mrad.

... This dependence is ascribed to the balance of painting emittance and its resultant space charge mitigation.

✓ Correlated painting provides narrower beam width.

. . . This situation can be understood by considering the effect of $2v_x-2v_y=0$.

Effects of the $2v_x - 2v_y = 0$ resonance

• Tune diagram near the operating point



- ✓ The $2v_x 2v_y = 0$ resonance is;
 - a 4th order systematic resonance,
 - excited mainly by the octupole component in the space-charge field,
 - causes emittance exchange between the horizontal and the vertical planes.
- ✓ The emittance exchange leads to two major effects

 (I) and (II)
 during the beam painting process.

Effects of the $2v_x - 2v_y = 0$ resonance (I)

- ✓ Additional emittance growth caused by the direct effect of emittance exchange
- ✓ More enhanced in correlated painting



- The emittance exchange occurs in the orthogonal direction to the direction of beam painting.
 - ⇒ The emittance exchange is directly connected to emittance growth over the painting area.

Effects of the $2v_x - 2v_y = 0$ resonance (II)

- ✓ Additional emittance growth caused by the secondary effect of emittance exchange namely, by a modulation of the charge density.
- ✓ More enhanced in anti-correlated painting.



Anti-correlated painting

- ✓ The direction of beam painting is the same as the direction of emittance exchange.
 - \Rightarrow Additional emittance growth caused by the direct effect of the emittance exchange is well suppressed.
- ✓ But, this situation causes a significant modulation of the charge density by synchronism between beam painting and emittance exchange.

Beam profile measurement



Space-charge de-tuning



The high density isle produces large space-charge detuning, leading to significant emittance growth afterwards.

<u>Correlated painting vs. anti-correlated painting</u>

✓ The emittance exchange caused by $2v_x-2v_y=0$ leads to two major effects during the beam painting process.

• <u>Effect (I);</u>

• Effect (II);

- Additional emittance growth caused by the direct effect of emittance exchange
- Additional emittance growth caused by the secondary effect of emittance exchange, namely, by a modulation of the charge density
- More enhanced in correlated paining More enhanced in anti-correlated painting



- \checkmark In the present operational condition, the emittance growth caused by (II) is more critical.
- ✓ Correlated painting avoids the effect. This is the main reason why narrower beam emittance is achieved for correlated painting.

Optimization of the tune and the chromaticity manipulations over the acceleration process

for mitigating additional emittance growth during acceleration

Emittance growth after injection



Mechanism of the emittance growth

• Time dependence of the tune footprint calculated at the first 1.6 ms to 8.7 ms



• 2d plot of turn-by-turn (J_x, J_y) of one macro-particle causing a large emittance growth on the vertical plane



- ✓ Similar emittance growth is generated also on the horizontal plane by v_x=6 & 2v_x-2v_y=0.
- ✓ Receiving the numerical simulation result, we tried to mitigate a part of emittance growth arising from v_{x,y}=6;
 - The tune & chromaticity were manipulated so as to separate the beam from $v_{x,y}=6$.

Operational parameters tested for emittance mitigation



Situation of the resonance cross to $v_{x,y} = 6$



- ✓ The separation from the integer lines is improved in the order $(A) \Rightarrow (B) \Rightarrow (C) \Rightarrow (D)$.
- ✓ The emittance growth should be mitigated step by step in this order.

Result of the emittance measurement

• Time dependence of the rms emittance for the first 7 ms



✓ The emittance growth was well mitigated in the order from (A) to (D), as predicted by the numerical simulation.

Remaining issue for the use of new parameters & its solution

Beam instability & its suppression

Beam instability

✓ Most dominant impedance source ; extraction pulse kickers

... causing horizontal beam instability depending on the operational parameters such as the choice of the tune and chromaticity.



- ✓ The parameters (C) and (D) well mitigate emittance growth for the first 6 ms, but enhance beam instability after 10 ms.
- ✓ This beam instability has to be solved for realizing the modified parameters (C) and (D).

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Practical solution

✓ Dynamically manipulating chromaticity over the acceleration process



 To realize the bipolar excitation of sextupole field, we improved the sextupole magnet power supply in the summer maintenance period in 2016. 23/27

Experimental result

with the bipolar excitation of sextupole field

- Turn-by-turn horizontal beam position over 20 ms Measurement 10 (A) 0 Dc excitation of sextupoles -10 10 (\mathbf{B}) **Bipolar** excitation of sextupoles 0 (und) 10 x **Measurement** 10 (C 0 0 -10 -10 10 10 (D D 0 0 -10 -10 10 16 18 8 12 14 20 12 16 2 2 4 6 8 10 14 18 20 0 0 Time (ms) Time (ms)
 - ✓ The beam instability was sufficiently damped as expected by introducing the bipolar excitation of the sextupole field.

Results of the extraction beam emittance

<u>& profile measurements</u>



- ✓ The extraction beam emittance including its tail part was successfully decreased from (A) to (D).
- This improvement of the extraction beam quality reflects the emittance growth mitigation achieved for the first 6 ms.

RCS parameter dependence of beam loss in MR

• <u>BLM signals at the MR collimator</u> measured for the RCS parameters of (A), (B) and (D)



- ✓ The MR beam loss was well reduced by 20% by the RCS parameter change from (A) to (B), while it was almost unchanged for the parameter change from (B) to (D).
- ✓ This result shows that the MR beam loss, arising from the RCS beam quality, is almost minimized by the parameter (D).
- MR beam tuning is in progress now with the improved RCS beam while steadily increasing the output beam power.
- ✓ The MR beam power for the NU experiment has recently reached a new record of ~470 kW.

Summary

 RCS is now ready to demonstrate a continuous 1-MW beam operation to MLF.

It will be conducted after the new high-power neutron target gets available.

For this past year, RCS intensively developed beam studies to realize a high-intensity low-emittance beam required from MR.

- The RCS beam emittance including its tail part was successfully decreased by optimizing
 - transverse injection painting,
 - tune & chromaticity manipulations,

where

- bipolar sextupole field patterns were newly introduced to simultaneously realize emittance growth mitigation at the early stage of acceleration and beam instability suppression after the middle stage of acceleration.

In addition, in this work, characteristic behaviours of beam particles during injection painting, appearing coupled with emittance exchange, was revealed.